



Atty. Docket No.: 15675.P322

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

C. Chappert

Application No.: 09/600,546

Filed: 7/12/00

For: **MAGNETIC ETCHING
PROCESS, ESPECIALLY FOR
MAGNETIC OR MAGNETO-
OPTIC RECORDING**

Mail Stop - NON-FEE - AMENDMENTS
Commissioner for Patents
PO Box 1450
Alexandria, Virginia 22313-1450

RECEIVED

FEB 24 2004.

RESPONSE TO OFFICE ACTION

Dear Commissioner:

This is in response to the outstanding Office Action mailed November 14, 2003.

In the Action, claims 1-6, 9-11, 14 and 17-19 are rejected under 35 U.S.C. 112, first paragraph, the Examiner taking the position that the limitation excluding ions of more than 16 AU atomic masses is unsupported by the specification. The Examiner contends the specification is devoid of any such teaching and referring to the portion of the specification cited by Applicant in this regard on page 4, lines 25-27, the Examiner contends recites "magnetic material (comprising a few atomic planes) is controllably irradiated in order to locally modify . . ."

*OK
LW
W
3/15/04*

In response, submitted herewith is a copy of page 4 from the specification wherein lines 25-27 have been highlighted containing language essentially identical to that which was added by amendment in the prior Office Action to claims 1 and 14.

Applicant has attempted to locate the portion of the specification quoted by the Examiner at page 2 of the Action but has been unable to identify any such portion.